



0.25µm GaN HEMT Library

Technology Overview

• Non-linear GaN HEMT models of 0.25 µm gate length HEMT operated at drain bias of 20 to 30 V for designing MMICs based on Angelov-GaN model for ADS are available in the library. In-house laboratory facilities for processing and metrology are used for establishing all the key device technologies. These facilities are available for timely updates of any device parameters whenever needed.

Core Technologies

- 0.25 µm gate length HEMT fabricated using 100KV e-beam direct writing
- Resistor : NiCr TFR ($20\Omega/\text{sq.}$), Mesa ($500\Omega/\text{sq.}$)
- Inductor: Rectangular, Circular
- Capacitor: MIM capacitors > 100V

Application Area and Advantages

- Library for designing broadband/high-power amplifiers GaN
- $f_t = 50 \text{ GHz} / V_{br} > 150 \text{ V}$
- Power density : 5 W/mm
- High temperature operation (up to 225°C)

Accomplishments

- GaN-dedicated laboratory available for stable operation and timely updates
- A number of intellectual properties including SCI papers and patents
- Licensing and/or joint research project for commercialization preferred







